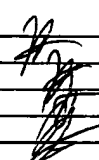
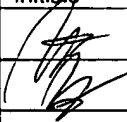


Substitute form 1449A/PTO				Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Application Number	To Be Assigned <u>10/689,152</u>
				Filing Date	Concurrently Herewith
				First Named Inventor	Won-Cheol Jeong
				Group Art Unit	
				Examiner Name	
Sheet	1	of	1	Attorney Docket Number	5649-1126

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Examiner Initials*	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
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		Office	Number	Kind Code (if known)			

OTHER NON PATENT LITERATURE DOCUMENTS				
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T	
	5	Durlam et al., <i>A low power 1Mbit MRAM based on 1T1MTJ bit cell integrated with Copper Interconnects</i> , 2002 Symposium on VLSI Circuits Digest of Technical Papers, 2002, pp. 158-161		
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Examiner Signature		Date Considered	
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.